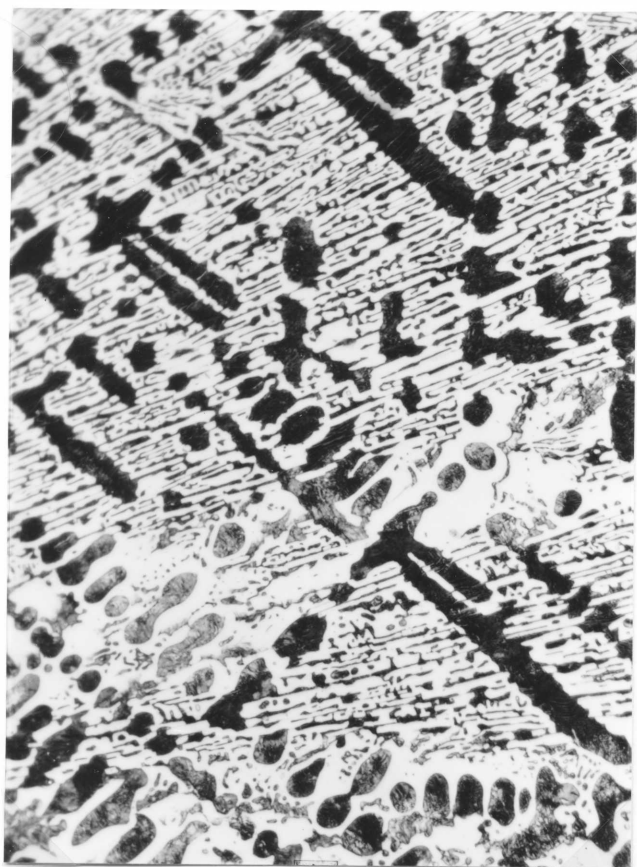
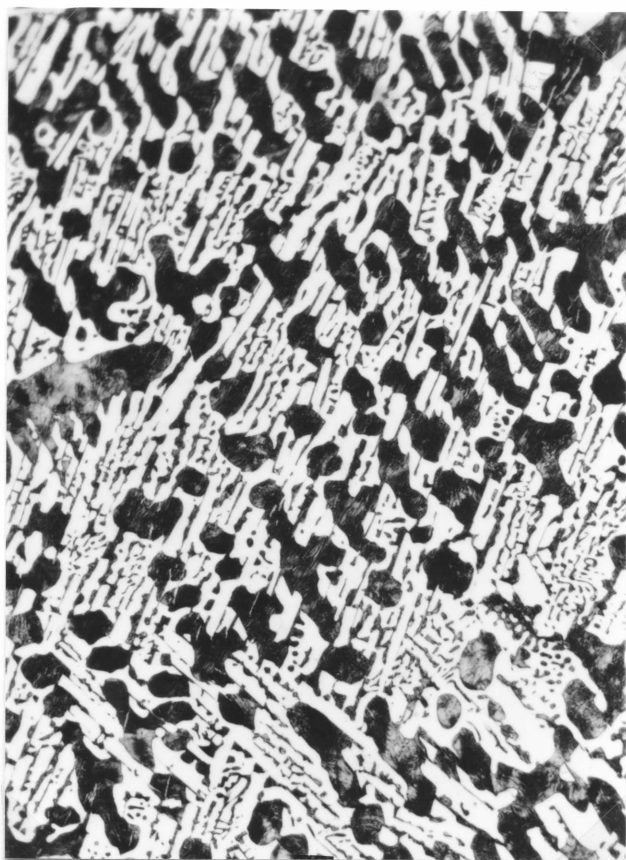


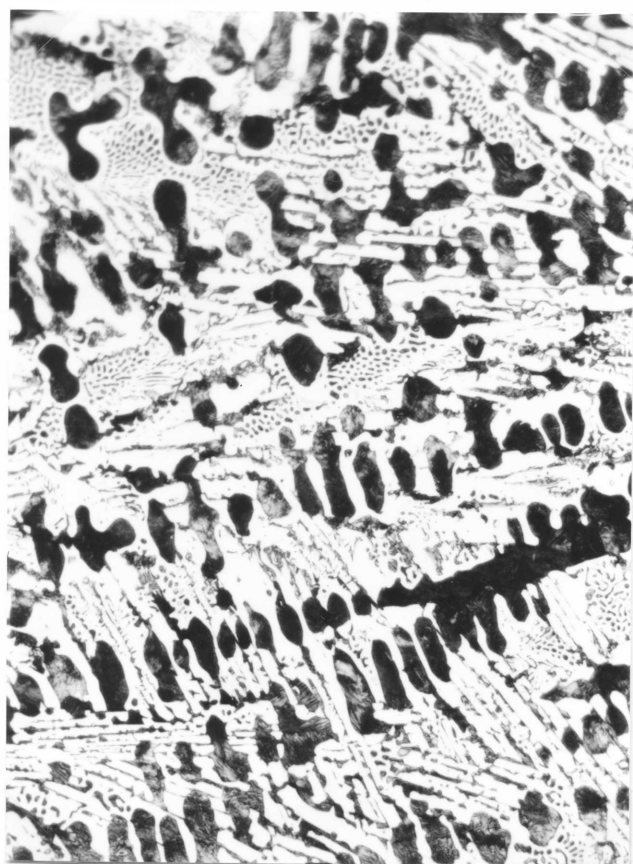
2800 - 3100: 0.10 - 0.99% Si, ca. 2.6 mm thick.  
As cast. Etched with nital, x750



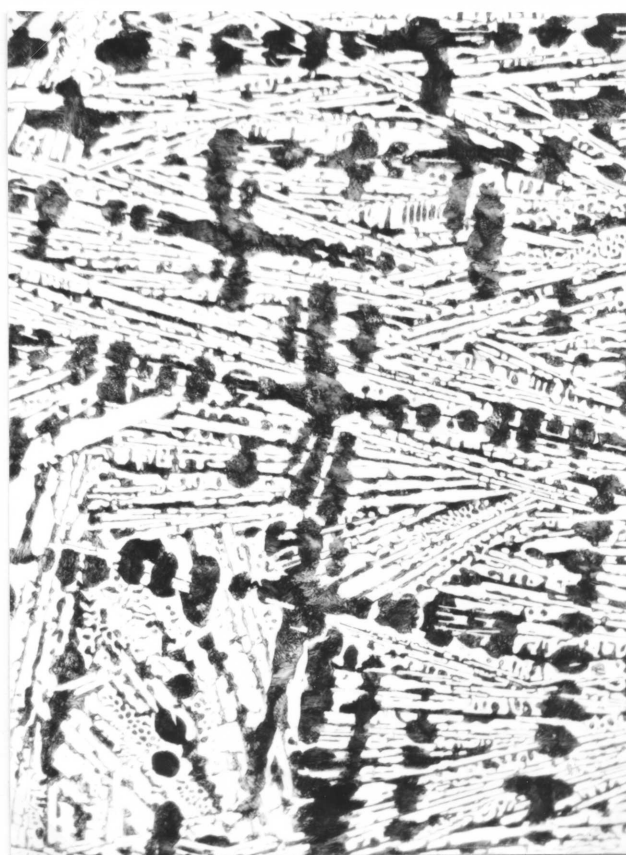
2800 0.10% Si



2900 0.20% Si

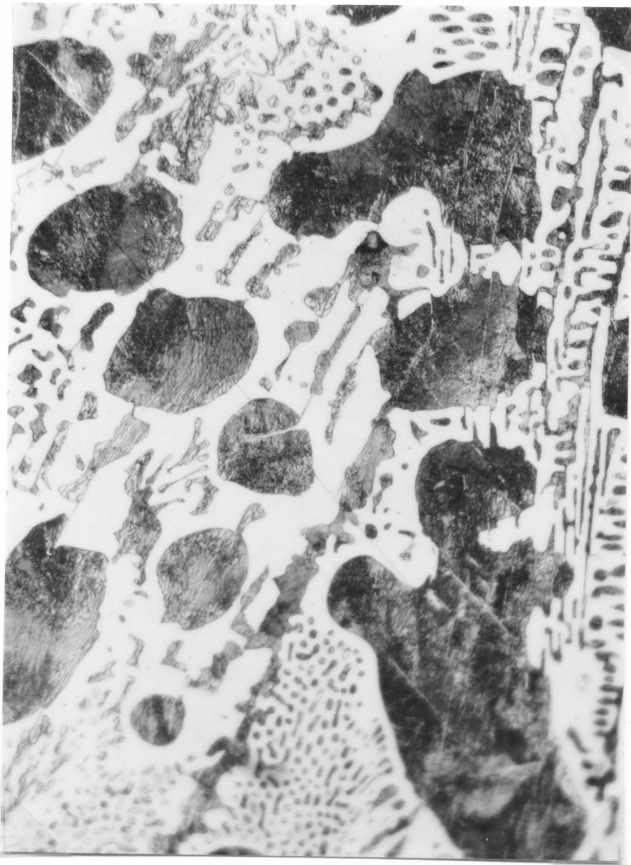


3000 0.47% Si

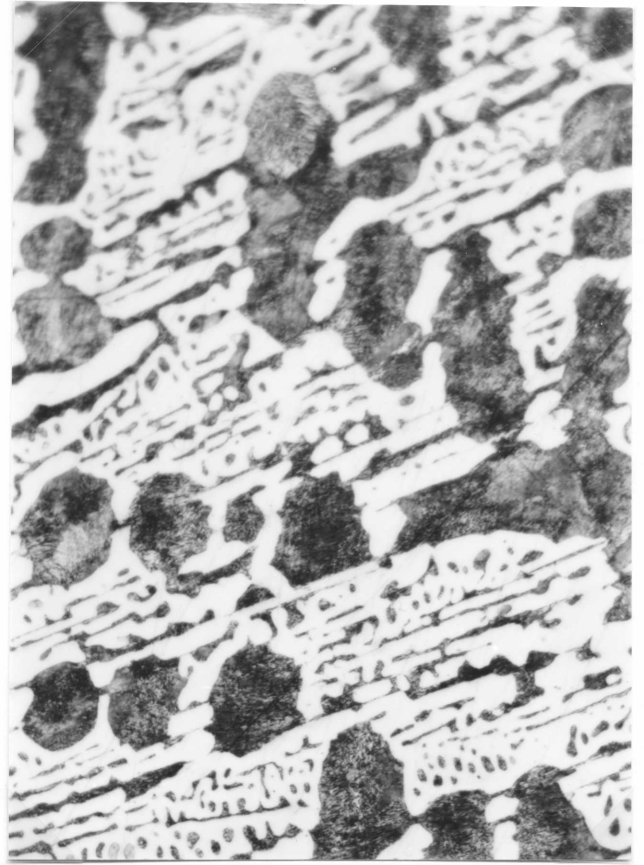


3100 0.99% Si

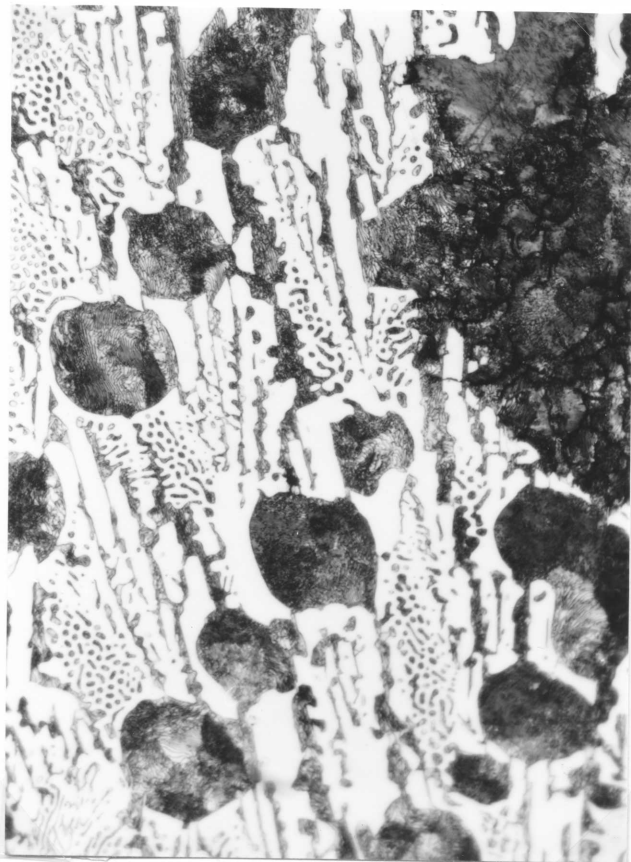
2810-3010: 0.10-0.99% Si, casting heads  
As cast. Etched with nital, x750



2810 0.10% Si



2910 0.20% Si

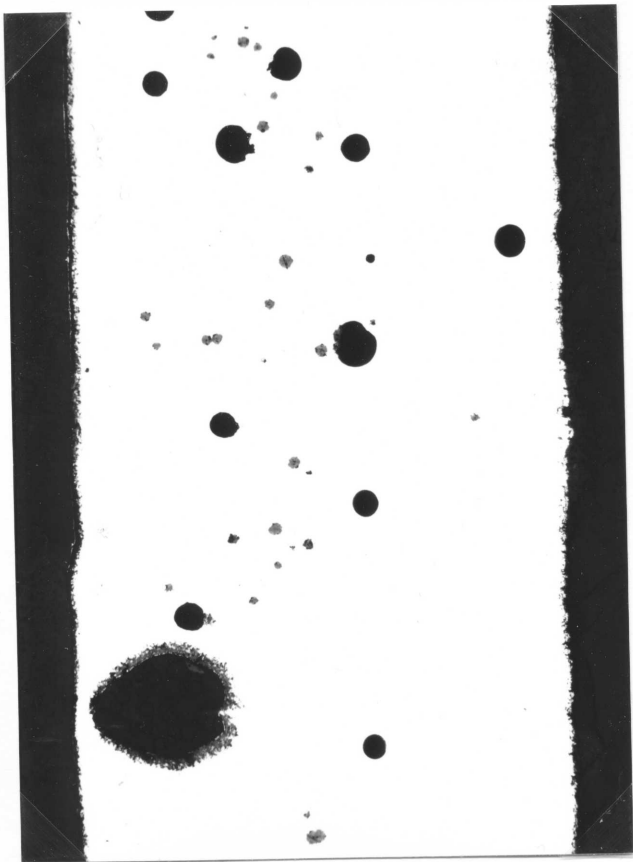


3010 0.47% Si

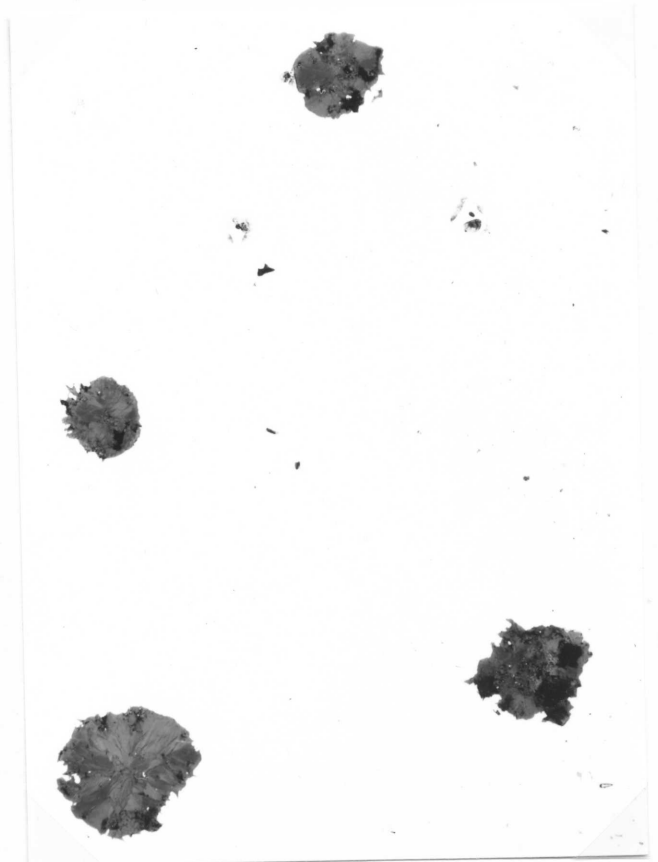
3110  
grey-cast

2801: 0.10% Si, <sup>2.5</sup>~~2.6~~ mm thick

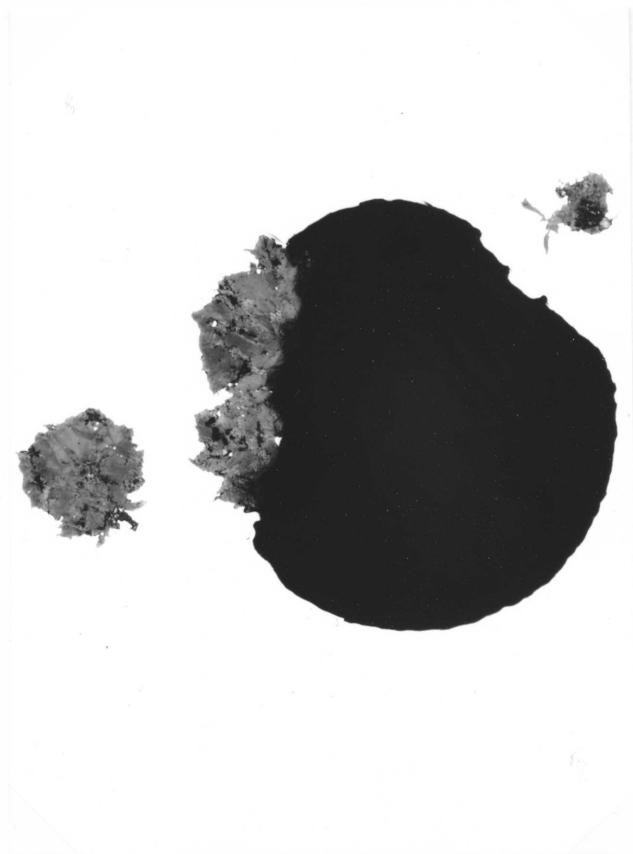
Annealed: 24 hr. at 400°C, 3 days at 950°C



unetched, x25



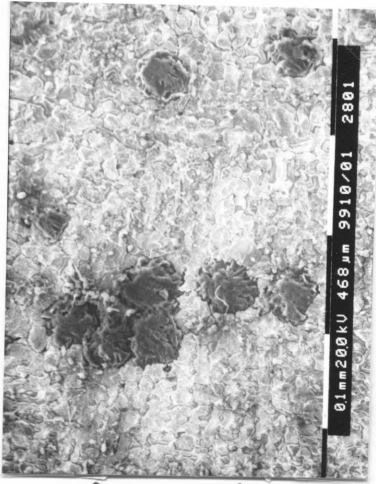
unetched, x250



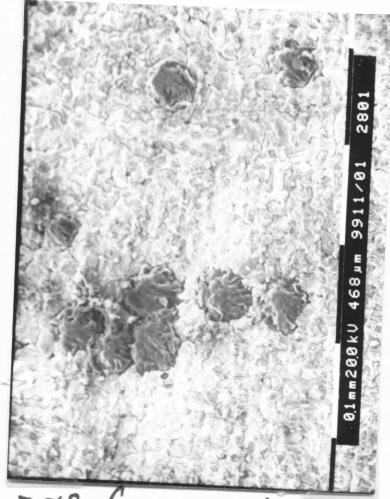
unetched, x250

2801, continued

Etched 105 min in 50% HNO<sub>3</sub>, ca. 60°C

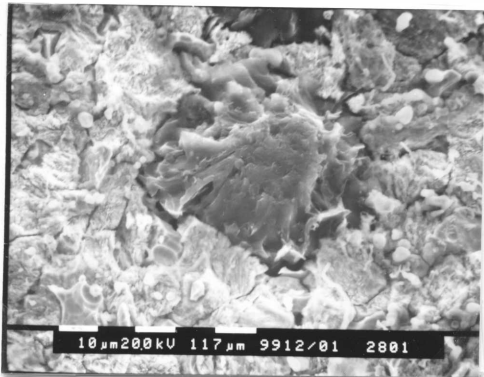


17° from vertical



28° from vertical

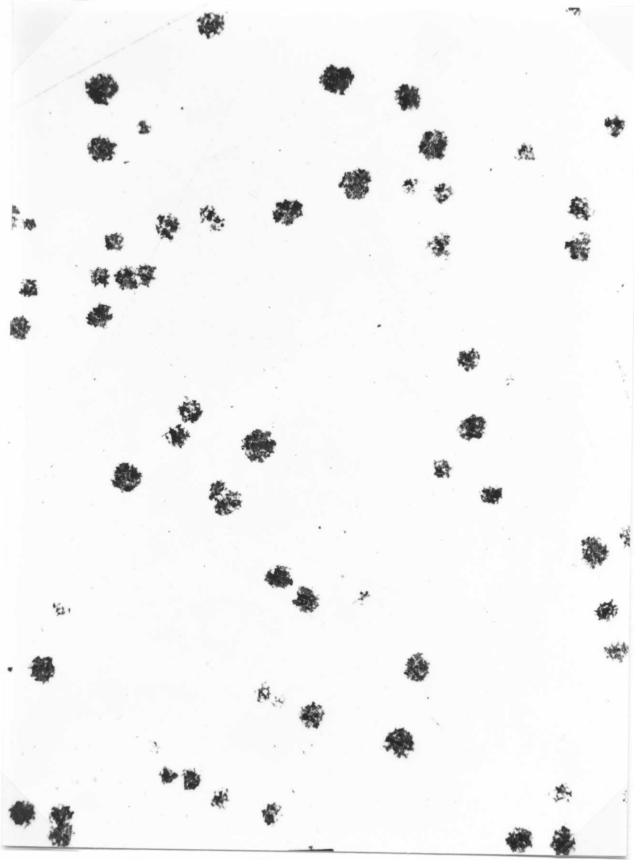
stereoscopic SEM, X125



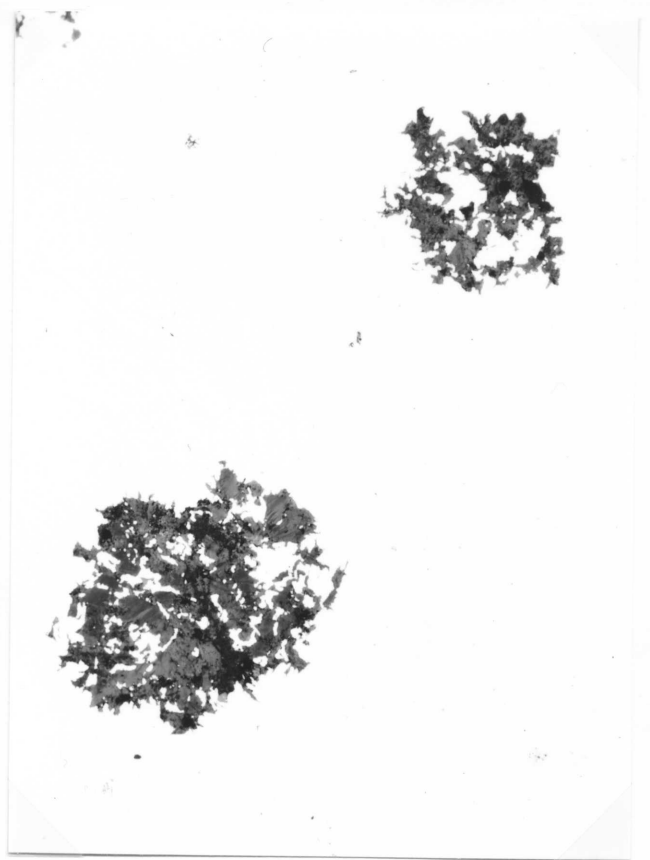
SEM, X500

2811: 0.10% Si, casting head

Annealed: 24 hr at 400°C, 3 days at 950°C



unetched, x25



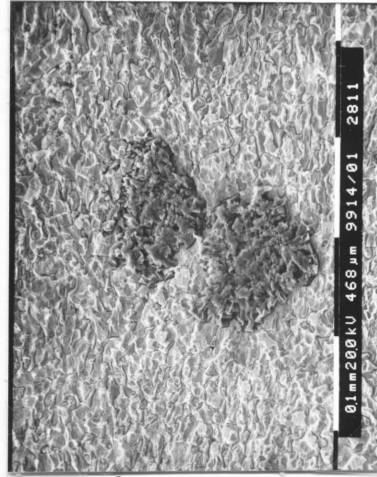
unetched, x250

2811, continued

Etched 105 min in <sup>30%</sup>~~50%~~ HNO<sub>3</sub>, ca. 60°C



17° from vertical

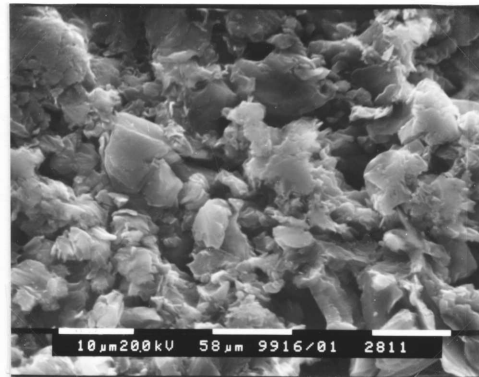


26° from vertical

stereoscopic SEM, x125



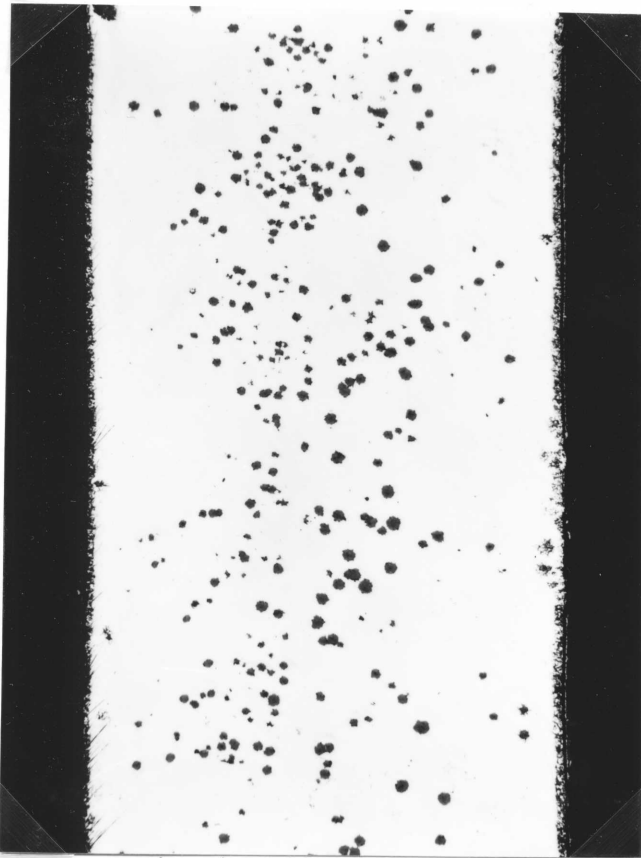
SEM, x500



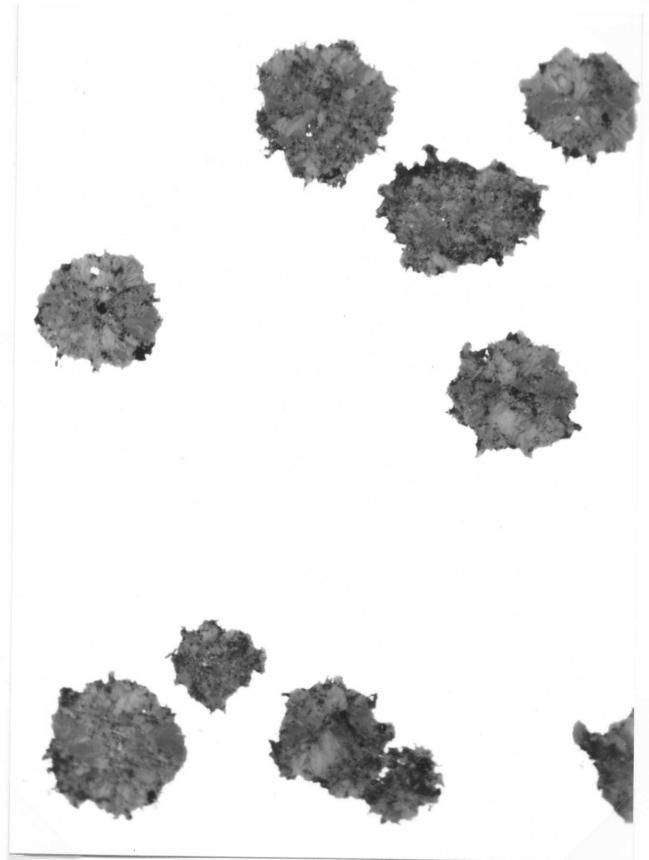
SEM, x1000

2901: 0.20% Si, 2.5 mm thick

Annealed: 24 hr at 400°C, 3 days at 950°C



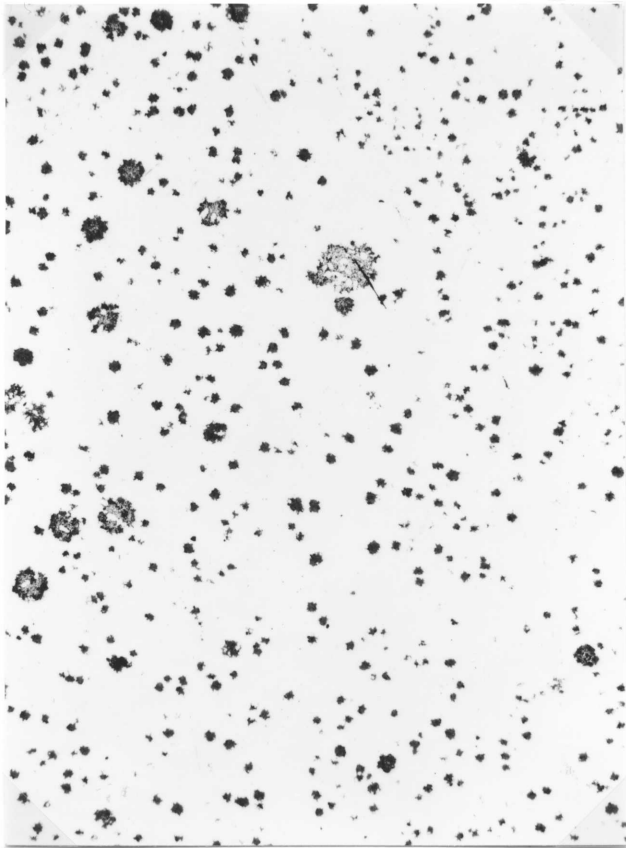
unetched, x 25



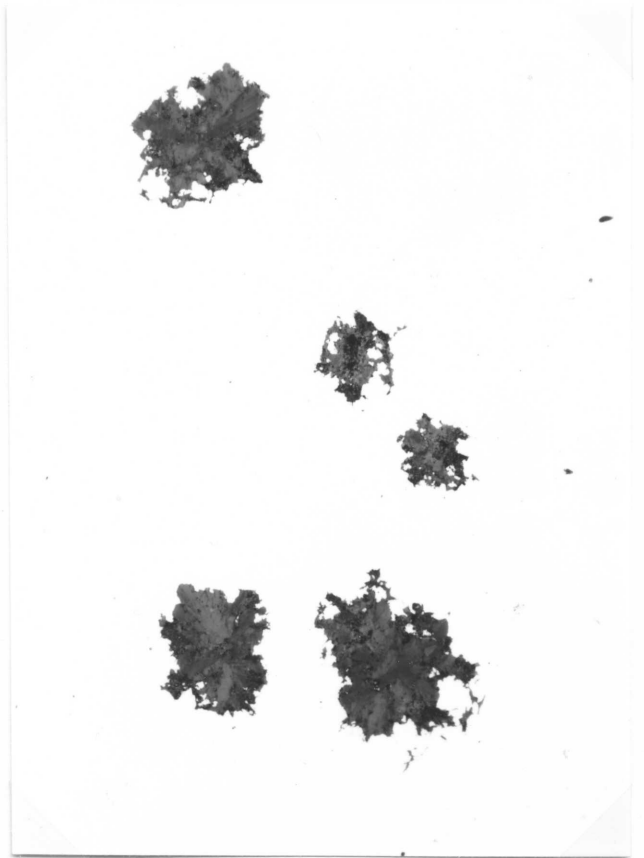
unetched, x 250

2911: 0.20% Si, casting head

Annealed: 24 hr at 400°C, 3 days at 950°C

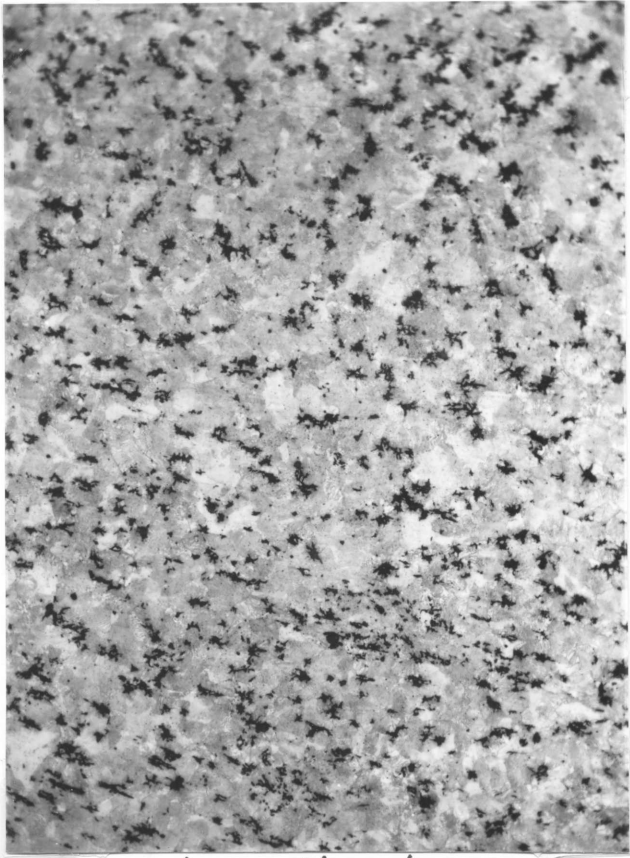


unetched, x25



unetched, x250

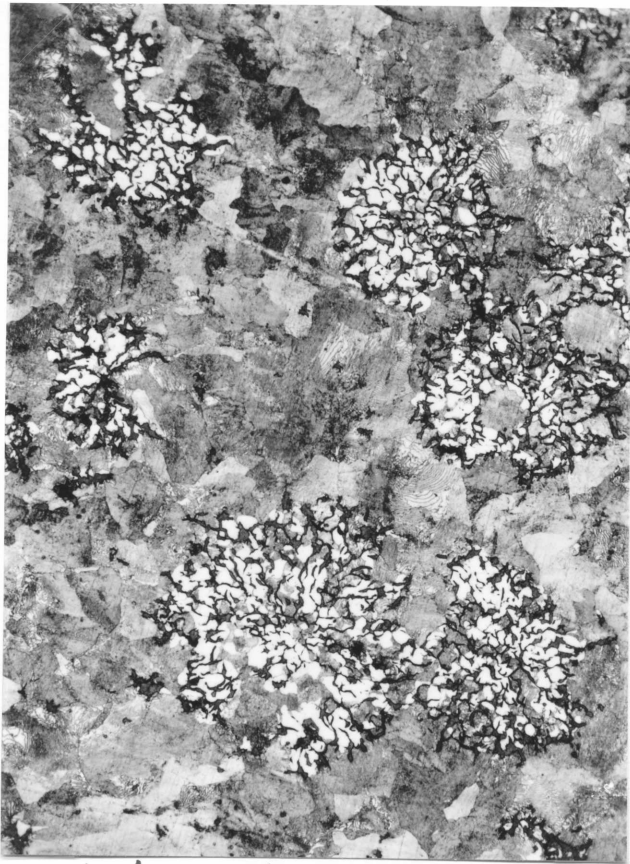
3001: 0.47% Si, 2.6 mm thick  
Annealed: 24 hr at 400°C, 3 days at 950°C



etched with nital, x250

3011: 0.47% Si, casting head

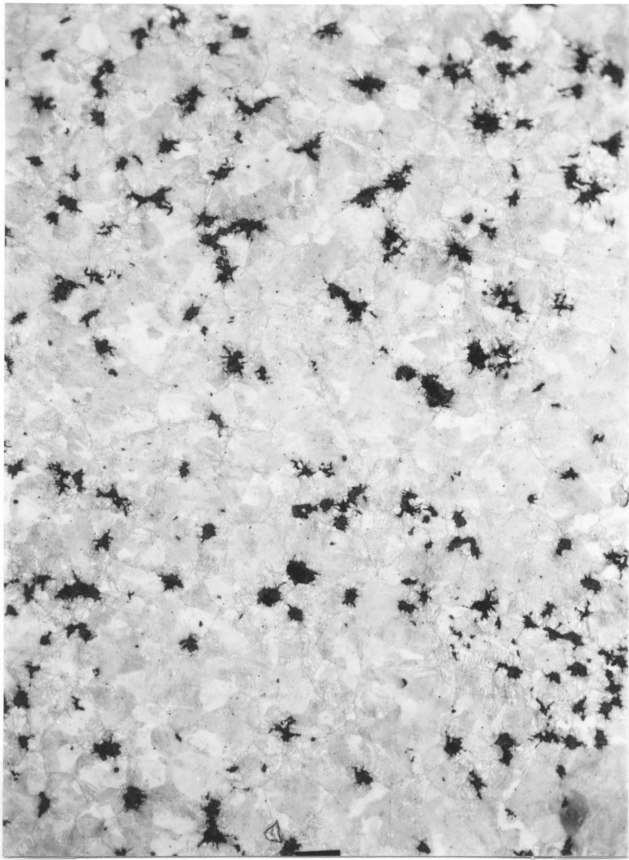
Annealed: 24 hr at 400°C, 3 days at 950°C



etched with nital, x250

3101: <sup>1.0</sup>~~0.99~~ % Si, 2.8 mm thick

Annealed: 24 hr at 400°C, 3 days at 950°C



etched with nital, x250